

Abstract

A polishing composition for a substrate for memory hard disk, comprising silica particles in an aqueous medium, wherein the silica particles satisfy a specified relationship between an average particle size of the silica particles on the number basis and a standard deviation on the number basis, wherein the average particle size is obtained by a determination by transmission electron microscope (TEM) observation, and wherein a particle size and a cumulative volume frequency in a range of particle sizes of from 60 to 120 nm satisfies a specified relationship; a method of reducing microwaviness of a substrate for memory hard disk, comprising the step of polishing the substrate for memory hard disk with the polishing composition; and a method for manufacturing a substrate for memory hard disk, comprising the step of polishing a Ni-P plated substrate for memory hard disk with the polishing composition. The method can be suitably used for the manufacture of a substrate for precision parts, such as a substrate for memory hard disk.